

Attorney Docket No.: SAM-03

Examiner: Nguyen, H.

Group Art Unit: 2812

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Serial No.:

Applicant(s): Soo-geun Lee, et al.

10/081,661

Filing Date:

February 22, 2002

Title:

METHOD OF MANUFACTURING INTERCONNECTION LINE IN

SEMICONDUCTOR DEVICE

CERTIFICATE OF MAILING UNDER 37 C.F.R. § 1.8

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Sir:

AMENDMENT AFTER FINAL REJECTION

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This is in response to the final Office Action mailed on March 6, 2003. It is requested. that the following amendments be entered and that the following remarks be considered 28

Please amend the application as follows:

## In the Claims

Please amend the claims as follows:

(Amended) A method of forming an interconnection line in a semiconductor 1. device comprising:

forming a first etching stopper on a lower conductive layer which is formed on a semiconductor substrate;

forming a first interlayer insulating layer on the first etching stopper;

forming a second etching stopper on the first interlayer insulating layer;

forming a second interlayer insulating layer on the second etching stopper;

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